

Lead Author

種別/Type	対象/Area	代表者/Lead author	共著者/Co-Author	題名/Title	発表先/Publication	Y	M	リンク/Link
講演/Lecture	国際/International	Hisashi Kitami	Junichi Nomoto, Toshiyuki Sakemi, Yutaka Furubayashi, Hisao Makino, Tetsuya Yamamoto	Manipulation of growth and oxygen-related point defects of Ga-doped ZnO polycrystalline films by controlling direct-current arc plasma	Material Research Meeting 2019 (MRM2019)	2019	11	https://mrm2019.jmru.org/
講演/Lecture	国際/International	Hisashi Kitami	Junichi Nomoto, Minoru Osada, Toshiyuki Sakemi, Yasushi Aoki, Hisao Makino, and Tetsuya Yamamoto	Deposition conditions limiting oxygen-related point defects of Ga-doped ZnO polycrystalline films deposited by ion-plating with direct-current arc discharge	29th International Conference on Defects in Semiconductors (ICDS-2017)	2017	8	http://www.icds2017.org/
講演/Lecture	国際/International	Hisashi Kitami	Junichi Nomoto, Toshiyuki Sakemi, Hisao Makino, Yasushi Aoki, and Tetsuya Yamamoto	Oxygen diffusion in electronegative-oxygen-ions irradiated Ga-doped ZnO polycrystalline films	30th International Conference on Defects in Semiconductors (ICDS-2017)	2017	8	http://www.icds2017.org/
講演/Lecture	国際/International	Hisashi Kitami	Toshiyuki Sakemi, Yasushi Aoki	Features of Incident Particle Flux determining Growth Rates and Electrical Properties of Indium Tin Oxide Films Deposited by Ion-plating with dc Arc Discharge	44rd International Conference on Metallurgical Coatings and Thin Films (ICMCTF2017)	2017	4	
講演/Lecture	国際/International	Hisashi Kitami	Junichi Nomoto, Toshiyuki Sakemi, Hisao Makino, Yasushi Aoki, Tetsuya Yamamoto	Effects of Incident Particle Fluxes on the Growth and Properties of Ga-doped ZnO Films Deposited by Ion-plating with dc Arc Discharge	44rd International Conference on Metallurgical Coatings and Thin Films (ICMCTF2017)	2017	4	
講演/Lecture	国際/International	Hisashi Kitami	Toshiyuki Sakemi, Yasushi Aoki	Characteristics of incident particle flux determining growth rates and electrical properties of indium tin oxide films deposited by ion-plating with dc arc discharge	26th Annual Meeting of MRS-J (2016): A-3 Advanced Functional Oxide Materials	2016	12	https://www.mrs-j.org/meeting2016/
講演/Lecture	国際/International	Hisashi Kitami	Junichi Nomoto, Toshiyuki Sakemi, Hisao Makino, Yasushi Aoki, Tetsuya Yamamoto	Influences of incident particle fluxes on the growth and properties of Ga-doped ZnO films deposited by ion-plating with dc arc discharge	26th Annual Meeting of MRS-J: A-3 Advanced Functional Oxide Materials	2016	12	https://www.mrs-j.org/meeting2016/
招待講演/Invited Lecture	国際/International	Hisashi Kitami (Invited)	Junichi Nomoto, Toshiyuki Sakemi, Hisao Makino, Yasushi Aoki, Tetsuya Yamamoto	Correlation between incident particle fluxes and growth rates of Ga doped ZnO films deposited by ion-plating with dc arc discharge	EMN Dalian Meeting 2016	2016	7	
招待講演/Invited Lecture	国際/International	Hisashi Kitami (Invited)	Junichi Nomoto, Toshiyuki Sakemi, Hisao Makino, Yasushi Aoki, Tetsuya Yamamoto, Takanori Kato	Control of the ratio of incident flux of ions to neutral species onto substrates to achieve high-carrier-mobility transparent conductive oxide films deposited by a high-growth-rate reactive plasma deposition	The Collaborative Conference on 3D and Materials Research (CC3DMR) 2016	2016	6	
講演/Lecture	国際/International	Hisashi Kitami	Junichi Nomoto, Hisao Makino, Toshiyuki Sakemi, Yasushi Aoki, Takanori Kato, Tetsuya Yamamoto	Characteristics of Incident Particle Flux Determining Growth Rates of ZnO Films Doped with Ga Atoms by Ion-plating with dc Arc Discharge	43rd International Conference on Metallurgical Coatings and Thin Films (ICMCTF2016)	2016	4	
講演/Lecture	国際/International	Hisashi Kitami	Kazuya Taki, Toshiyuki Sakemi, Yasushi Aoki, Takanori Kato	Correlation between the energy of depositing particles and the mobility of ITO films in Reactive Plasma Deposition with dc arc discharge	9th International Conference on Reactive Plasmas & 68th Gaseous Electric Conference & 33rd Symposium on Plasma Processing (ICRP-9/GEC-68/SPP-33)	2015	10	http://www.plasma.engg.nagoya-u.ac.jp/icrp-9/
講演・受賞/Lecture, award	国際/International	Hisashi Kitami (Prize)	Masaru Miyashita, Toshiyuki Sakemi, Yasushi Aoki, Takanori Kato	Dependence of Electron Mobility of ITO Films on Energy of Depositing Particles in Reactive Plasma Deposition	Plasma Conference 2014	2014	11	http://www.ispf.or.jp/PLASMA2014/jpn/
講演/Lecture	国際/International	Hisashi Kitami	Masaru Miyashita, Toshiyuki Sakemi, Yasushi Aoki, Takanori Kato	Quantitative analysis of ionization rates of depositing particles in reactive plasma deposition equipment using mass-energy analyzer and Langmuir probe	8th International Conference on Reactive Plasmas & 31st Symposium on Plasma Processing (ICRP-8/SPP-31)	2014	2	
講演/Lecture	国際/International	Hisashi Kitami	Masaru Miyashita, Toshiyuki Sakemi, Ryotaro Kaneko, Kensaku Tanaka, Rei Kawashima, Yasushi Aoki, Takanori Kato, Yoshihiro Arakawa	Comparison of Plasma Simulation and Experimental Results on Axisymmetric Plasmas	The 19th Annual Meeting of Institute of Applied Plasma Science & The Fifth International Workshop on Plasma Application & Hybrid Functionally Materials (IAPS2012)	2012	3	
講演/Lecture	国際/International	T. Sakemi	S. Shirakata, K. Iwata, K. Matsubara, H. Tambo, P. Fons, S. Niki, K. Awai, T. Yamamoto	High-Quality Transparent Conducting Oxide Films Deposited by a Novel Ion Plating Technique	2003 MRS Spring Meeting	2003	4	https://doi.org/10.1557/PROC-763-B7.4
講演・投稿/Lecture, Research paper	国際/International	Shin Masui	Kimio Kinoshita, Susumu Sakuragi, Toshio Kudo, Shinji Takayama	Highly (111) Oriented Al Thin Films by Ion-Plating Method Using Discharge Plasma	2001 MRS Spring Meeting	2001	4	https://doi.org/10.1557/PROC-714-L8.6.1
講演/Lecture	国際/International	Toshiyuki Sakemi		Pressure gradient type plasma source and ITO ionplating	The 10th Iketani Conference on Materials Research Toward The 21st Century	2000	6	https://www.iketani-zaidan.or.jp/prom/index3.html
講演・投稿/Lecture, Research paper	国際/International	T. KUDO	S. SAKURAGI, S. MASUI, K. KINOSHITA, H. MAKINO, M. TANAKA	Strongly (111) Oriented Metallization by Ion Plating Method	2000 MRS Spring Meeting	2000	4	https://doi.org/10.1557/PROC-616-205
講演/Lecture	国際/International	Hiroyuki Makino	Masaru Tanaka, Kiyoshi Awai	New ion plating process for film deposition of Cu wiring	The 15th International VLSI Multilevel Interconnection Conference	1998		
講演/Lecture	国際/International	T. Suzuki	M. Tanaka, R. Chikugo, K. Yoshida, H. Uchiike	MgO deposition by new ion-plating process	The 4th International Display Workshops	1997	11	